Claims

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1. A power amplifier system using as an amplifying element a Schottky barrier gate metal semiconductor field effect transistor ("MESFET") with a source grounded for receiving a drain bias voltage and a forward gate bias voltage of zero or a low potential as supplied from a unipolar power supply and for amplifying an input signal superposed with said gate bias voltage to output an amplified signal indicative of a change in drain current, characterized in that

said MESFET permits, upon application of a forward direct current (DC) gate voltage to a gate terminal with a source terminal grounded, the DC gate voltage to be greater than or equal in value to 0.65 volt (V), said DC gate voltage causing a gate current value per gate width of 100 micrometers (μ m) to go beyond 100 microamperes (μ A).

- The power amplifier system as recited in
 claim 1, characterized in that said MESFET is a MESFET of shallow depression type or enhancement type.
 - 3. The power amplifier system, characterized in that said MESFET has a channel region comprised of a compound semiconductive material of direct transition type.

- 4. The power amplifier system as recited in any one of the preceding claims 1 to 3, characterized in that a circuit for supplying said gate bias voltage is equipped with a ripple filtering capacitor.
- 5. The power amplifier system as recited in claim 4, characterized in that said ripple filtering capacitor is provided outside of a semiconductor substrate with said MESFET formed thereon.

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- one of the preceding claims 1 to 5, characterized in that a layer made from an alloy of a metal constituting said gate electrode and semiconductor constituting said channel region is formed at an interface between the gate electrode and channel region of said MESFET.
 - 7. The power amplifier system as recited in claim 6, characterized in that said metal is greater in work function than tungsten silicides.
- 8. The power amplifier system as recited in claim 7, characterized in that said metal is selected from the group consisting of platinum (Pt) and palladium (Pd).
 - 9. The power amplifier system as recited in any one of the preceding claims 1 to 8, characterized in that said MESFET is formed separately per

semiconductor substrate and that said MESFET and a passive element are arranged in a way independent of each other.

10. The power amplifier system as recited in any one of the preceding claims 1 to 8, characterized in that said MESFET and a passive element for use in making up amplifier circuitry are formed on a single semiconductor substrate.

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- any one of the preceding claims 1 to 8, characterized in that said MESFET and a passive element for use in making up amplifier circuitry plus output matching circuitry of said amplification circuitry are formed together on a single semiconductor substrate.
 - having a power amplifier circuit including a compound semiconductor MESFET for use as an active element for amplifying and outputting a high frequency signal, the MESFET having a source coupled to ground, a unipolar power supply for supplying said compound semiconductor MESFET with a drain bias voltage and a gate bias voltage, and an output matching circuit of said power amplifier circuit, characterized in that

said compound semiconductor MESFET permits, upon application of a forward direct current (DC) gate

voltage to a gate terminal with its source terminal grounded, the DC gate voltage to be greater than or equal in value to 0.65 volt (V), said DC gate voltage causing a gate current value per gate width of 100 micrometers (μm) to go beyond 100 microamperes (μA) .

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- 13. The mobile communications terminal device as recited in claim 12, characterized in that a circuit for supplying said gate bias voltage is associated with a ripple filter capacitor as connected thereto and provided outside of a semiconductor substrate with said MESFET formed thereon.
- 14. The mobile communications terminal device as recited in claim 12 or 13, characterized in that said compound semiconductor MESFET has a gate electrode and a channel region made of compound semiconductor defining therebetween an interface with a layer made from an alloy of a metal and said compound semiconductor formed thereat, said metal being selected from the group consisting of platinum (Pt) and palladium (Pd). 20